

SPUTTERING TARGET, METHOD FOR PRODUCING LAMINATED FILM,
LAMINATED FILM AND MAGNETIC RECORDING MEDIUM

ABSTRACT

A sputtering target according to the present invention contains Co and Pt as metal components, wherein a molar ratio of a content of Pt to a content of Co is from 5/100 to 45/100, and wherein the sputtering target contains Nb_2O_5 as a metal oxide component.